



PATENT Customer No. 22,852 Attorney Docket No. 04329.3238

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re A	Application of:	)	
Gaku MINAMIHABA et al.		Group Art Unit: 2818	
Application No.: 10/771,060		)	Examiner: Goodwin, David J.
Filed:	February 4, 2004	)	Confirmation No. 2231
For:	POLISHING PAD AND METHOR OF MANUFACTURING SEMICONDUCTOR DEVICES	) ) )	
P.O. E	nissioner for Patents Box 1450 ndria, VA 22313-1450		
Sir:			

## RESPONSE TO RESTRICTION REQUIREMENT

In the Restriction Requirement mailed September 15, 2005, with a period for response extending to October 17, 2005 (October 15<sup>th</sup> being a Saturday), the Examiner required restriction under 35 U.S.C. § 121 between Group I (claims 1-10) and Group II (claims 11-20). Applicants elect to prosecute Group II, claims 11-20, characterized by the Examiner as drawn to a method of making a semiconductor device, without traverse.

Please grant any extensions of time required to enter this response and charge any additional required fees to our deposit account 06-0916.

Respectfully submitted,

FINNEGAN, HENDERSON, FARABOW,

GARRETT & DUNNER, L.L.P.

Dated: October 17, 2005

David M. Longo

Reg. No. 53,235